

Strengths of IC enhancement-mode GaN

CS International Conference – Brussels, 04/17/2024 Andrea Bricconi - CCO

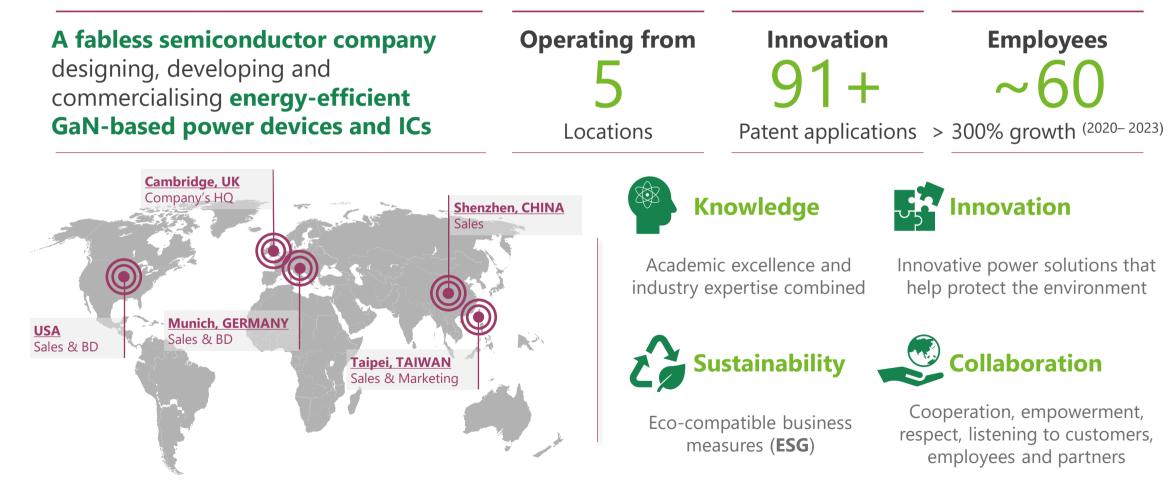
> camgandevices.com © 2024 CGD

Property of Cambridge GaN Devices Ltd.

Cambridge GaN Devices at a Glance

The fast-paced scaleup making green electronics possible





Figures of Merit, Key 600-650 V Power Technologies



Figure of Merit	Si Superjunction *	SiC *	GaN (vs incumbent)	Comments
R _{DS(On)} x Area	100%	20%	30%	Density, Weight, Cost
R _{DS(On)} x Q _{rr}	100%	10%	0	Half Bridge, hard commutation
R _{DS(On)} x E _{oss}	100%	123%	80%	Switching losses, efficiency in e.g. classic PFC
R _{DS(On)} x Q _g	100%	90%	8%	Driving losses, light load efficiency
R _{DS(On)} x Q _{OSS}	100%	17%	10%	Efficiency at high frequency, soft switching
Ease of Use	High	High	Low/Medium	Si and SiC well established
Robustness	High	High	Low/Medium	and understood
Technology	Vertical	Vertical	Lateral	GaN enables integration

* Specific technologies selected

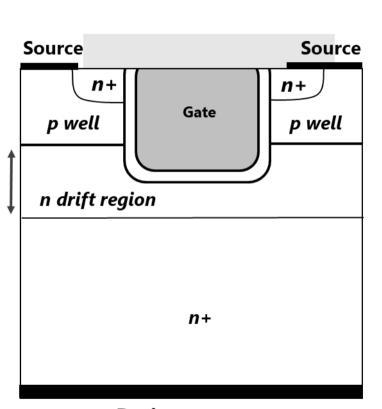
Figures of Merit, Key 600-650 V Power Technologies



Figure of Merit	Si Superjunction *	SiC *	GaN (vs incumbent)	Comments
Ease of Use	High	High	Low/Medium	Si and SiC well established and understood
Robustness	High	High	Low/Medium	
Technology	Vertical	Vertical	Lateral	GaN enables integration

Vertical vs Lateral: Basics and Consequences

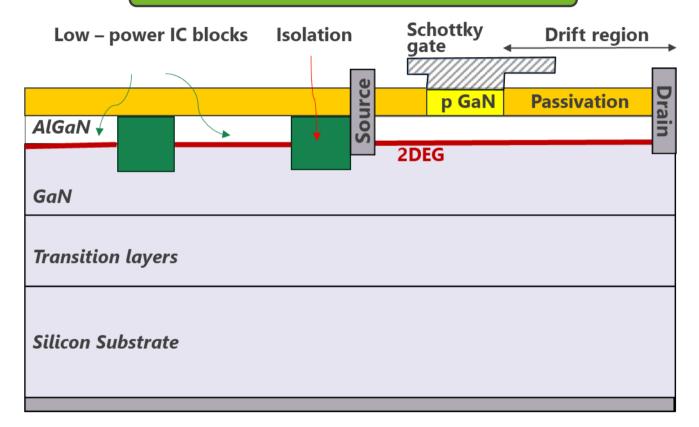




SiC MOSFET– Schematic cross section

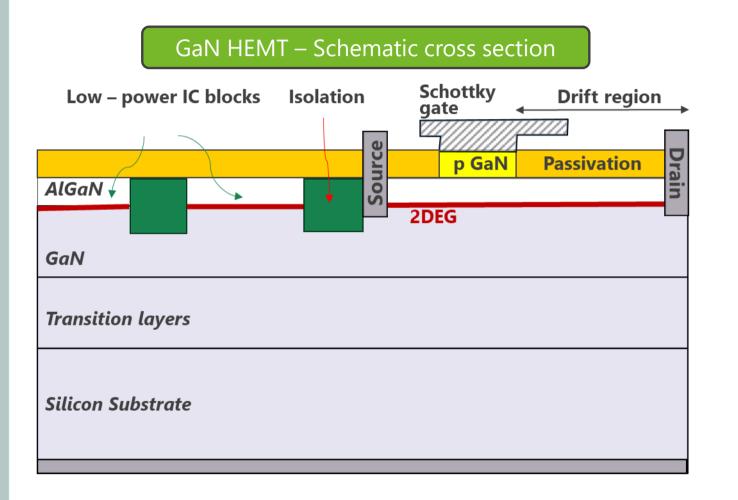


GaN HEMT – Schematic cross section



Vertical vs Lateral: Basics and Consequences



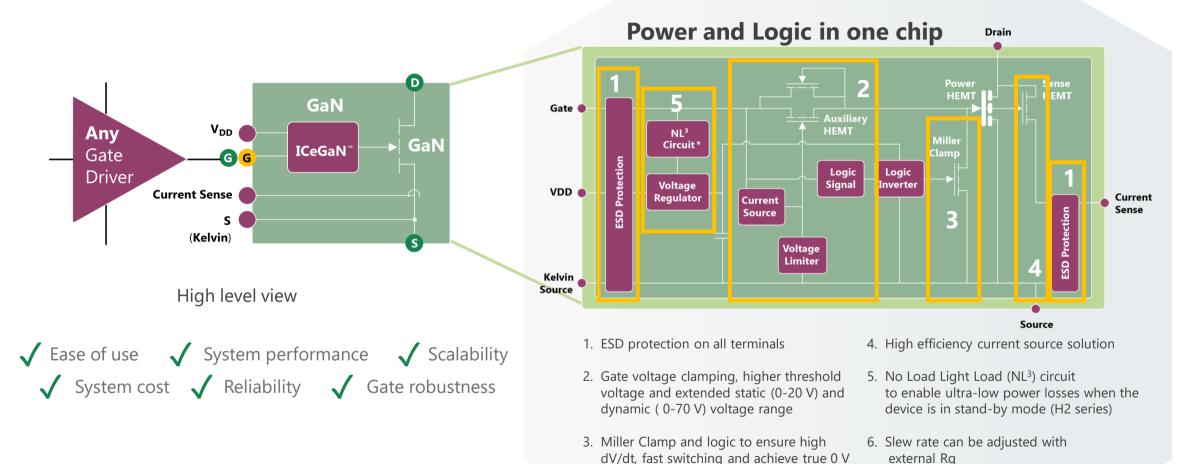


- Due to lateral technology, GaN can incorporate a power HEMT and adjacent, isolated circuit blocks.
- Unlike in vertical switching devices, the substrate does not switch and this offers safer vertical isolation.
- Lateral isolation is provided through isolation regions which remove the 2DEG underneath.
- Integration of multiple structures require the availability of HV and LV cells in the same chip.
- CGD partner with TSMC, all processes are available.

Decades of Research Led to ICeGaN™

Combined system performance and ease of use





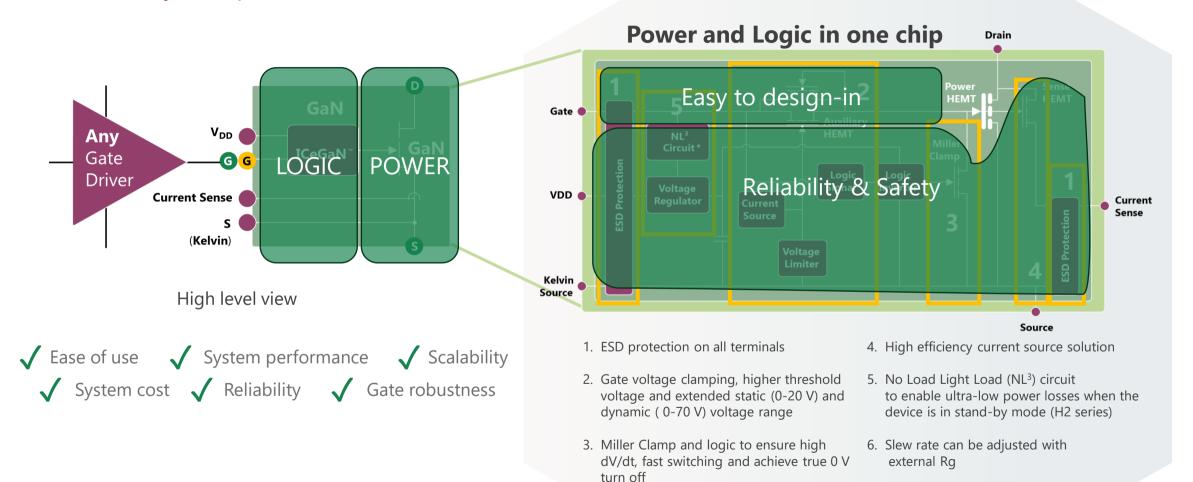
Property of Cambridge GaN Devices Ltd.

turn off

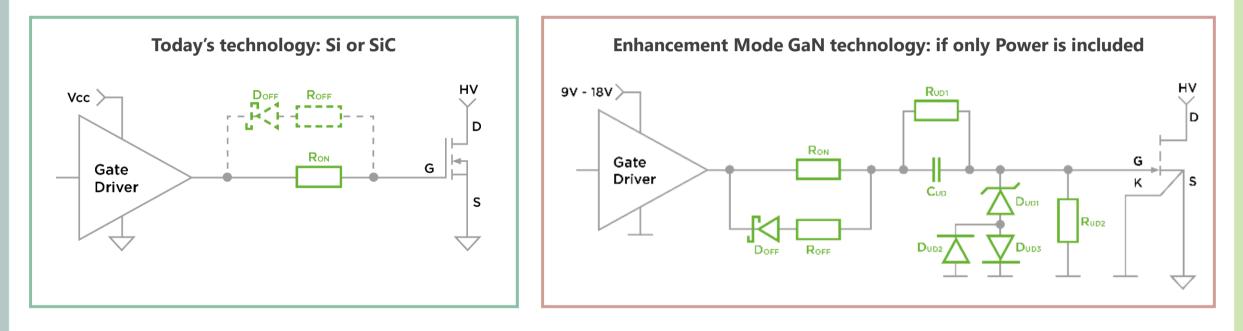
Decades of Research Led to ICeGaN™

Combined system performance and ease of use





eMode GaN HEMT Is Very Different from MOSFET Discrete GaN, complex and costly driving circuits are needed



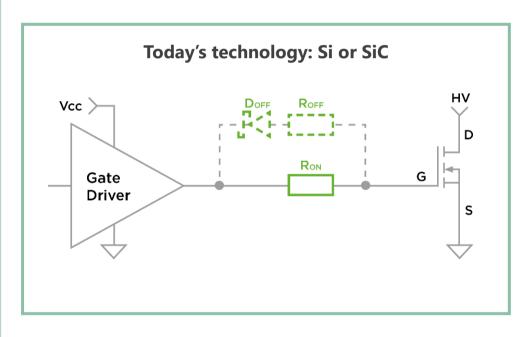
O

CAMBRIDGE GaN DEVICES

eMode GaN HEMT Is Very Different from MOSFET





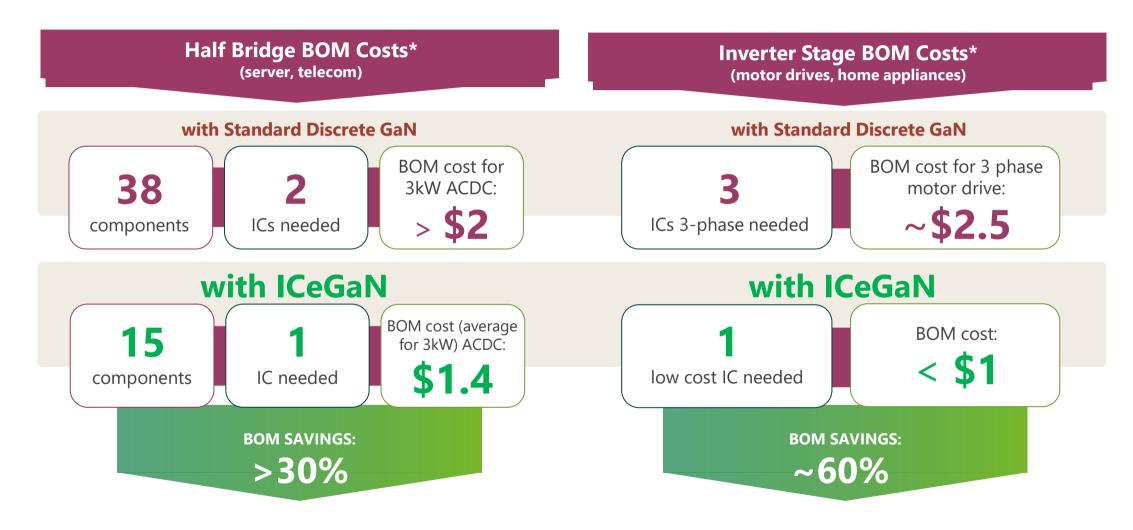


- Threshold Voltage shifted to 3 V
- Outer Gate Voltage up to 20 V
- Inner Gate Voltage is temperature dependent
- TurnOFF is ensured at 0 V, no negative Voltage needed
- dV/dt immunity, gate robustness
- Easy paralleling of multiple GaN HEMTs
- Significant BOM and \$ savings

ICeGaN[™]: \$ Advantage - High Power

If Logic and Power work together: advantage for Half Bridge topologies





ICeGaN™: Performance Advantage



Improved device/system robustness and efficiency for low and high power applications

Robustness Gate under Dynamic Voltage

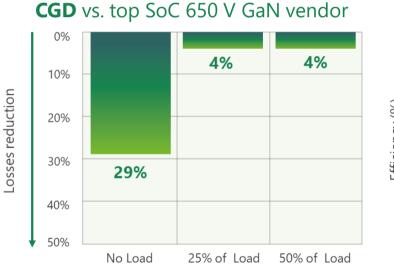
Technology	25°C	150°C
ICeGaN	84 V	92 V
Si IGBT	80 V	80 V
SIC MOSFET	70 V	70 V
Std eMode GaN	24 V	25 V



B. Wang et al "Exceptional Gate Overvoltage Robustness in P-Gate GaN HEMT with Integrated Circuit Interface", APEC 2024 **Efficiency for Low Power**

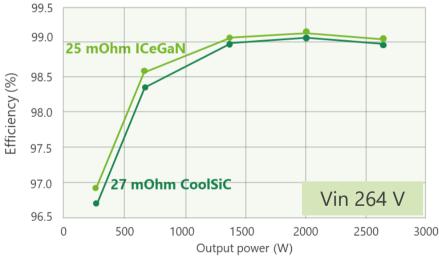
No Load / Light Load losses

65 W – USB-PD QR flyback



Efficiency for High Power ICeGaN vs Si Carbide

3.2 kW – TotemPole PFC **CGD** vs. top 650 V SiC vendor



Summary and Conclusions



- GaN HEMTs are the present and future of Power Conversion and are manufactured in high volumes.
- GaN potential can be better exploited by integrating Logic and Power, like in the ICeGaN.
- Robustness and Reliability are same or better than incumbent Si / SiC technologies.
- Economy of scale will make it the technology of choice, beyond what was initially envisioned...Automotive included.

13